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### **Application Information**

Title Line One:: MASK, EXPOSURE METHOD, LINE WIDTH  
Title Line Two:: MEASURING METHOD, AND METHOD FOR  
Title Line Three:: MANUFACTURING SEMICONDUCTOR DEVICES

Title Line Four::  
Total Drawing Sheets:: 16  
Docket Number:: 108057

**Continuity Information**

>This application is a::  
Application One::  
Filing Date::  
Patent Number::  
which is a::  
>>Application Two::  
Filing Date::  
Patent Number::

**Prior Foreign Applications**

Foreign Application One:: 11-348196  
Filing Date:: December 7, 1999  
Country:: Japan  
Priority Claimed:: yes  
Foreign Application Two::  
Filing Date::  
Country::  
Priority Claimed::  
Foreign Application Three::  
Filing Date::  
Country::  
Priority Claimed::